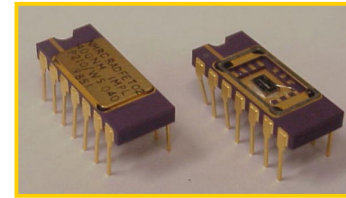


Modelling packaging effects on proton irradiation response of NMRC RadFETs

New GEANT4 simulations



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Previous observations indicate RadFET response :

- may depend on proton energy
- varies with the package configuration.

In this work GEANT4 has been used to :

- Analyse the influence of the RadFET package on the proton response for different energies.
- Compare simulated and experimental results, using the ratio between the primary and secondary total ionising dose contributions for different packaging configurations.



- Introduction
 - NMRC RadFET description and Geometry
 - Briefly: Physics Models
 - Simulation scheme
- Proton beams
- Simulated Response:
 - Primary TID vs. Proton energy
 - Secondary TID vs. Proton energy
 - Primary vs. Secondary TID
 - Package effect
 - Secondary particles
- Simulation/Experimental results
 - 10MeV case: considerations
- Conclusions
 - Further work: possible improvements



Global scope:

- Learn how to predict component radiation behaviour in space by performing lab experiments and simulations.

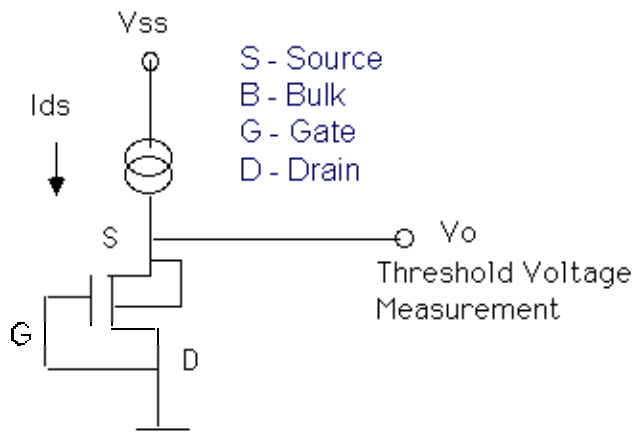
Work description:

- Proton beams simulated according to PSI beam profiles for 10, 60 and 300 MeV.
- Employ the GEANT4 to quantify TID contribution from secondary particles generated in the RadFET package and Gate Oxide.

NMRC RadFET description



- MOSFET based dosimeter with optimised gate-oxide for increased radiation sensitivity.
- Induces charge trapping in the gate oxide and at Si/SiO₂ interface → threshold voltage shift : $\Delta V_o = f(TD)$



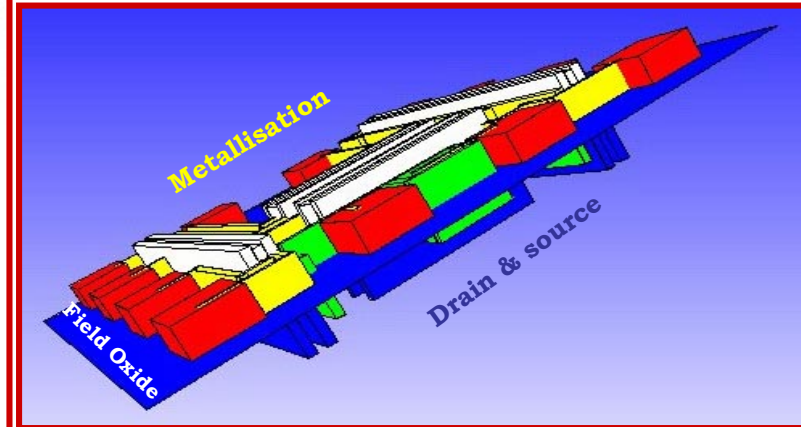
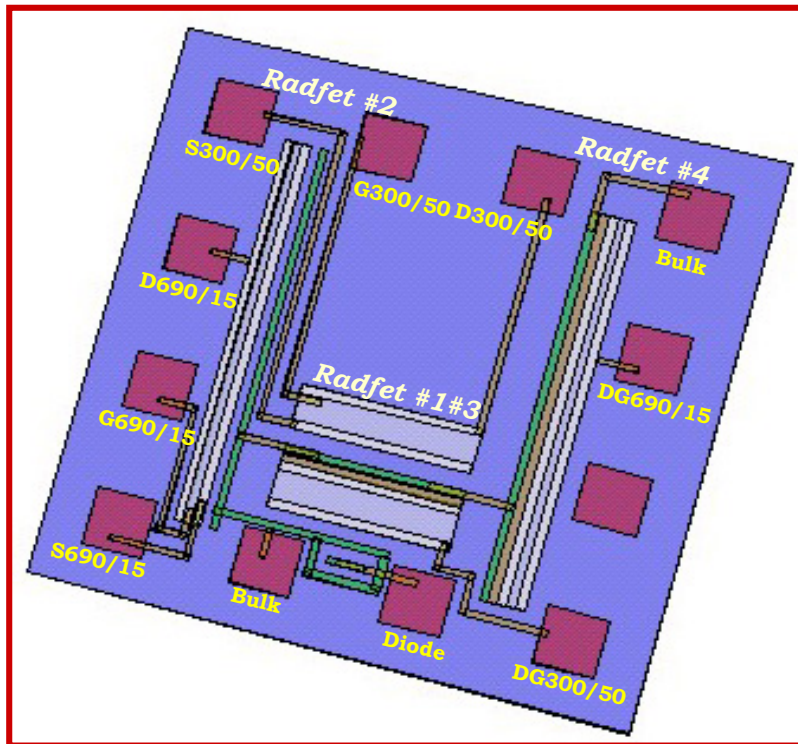
Vo is measured by:

- applying a constant current (I_{ds}) and measuring the source-drain voltage.
- Due to the constant current, the source-drain voltage increases as the irradiation induced charge build-up in the gate oxide increases.
- I_{ds} is typically of 10 μ A.
- Drain is shorted to gate and source is shorted to bulk.

NMRC RadFET description

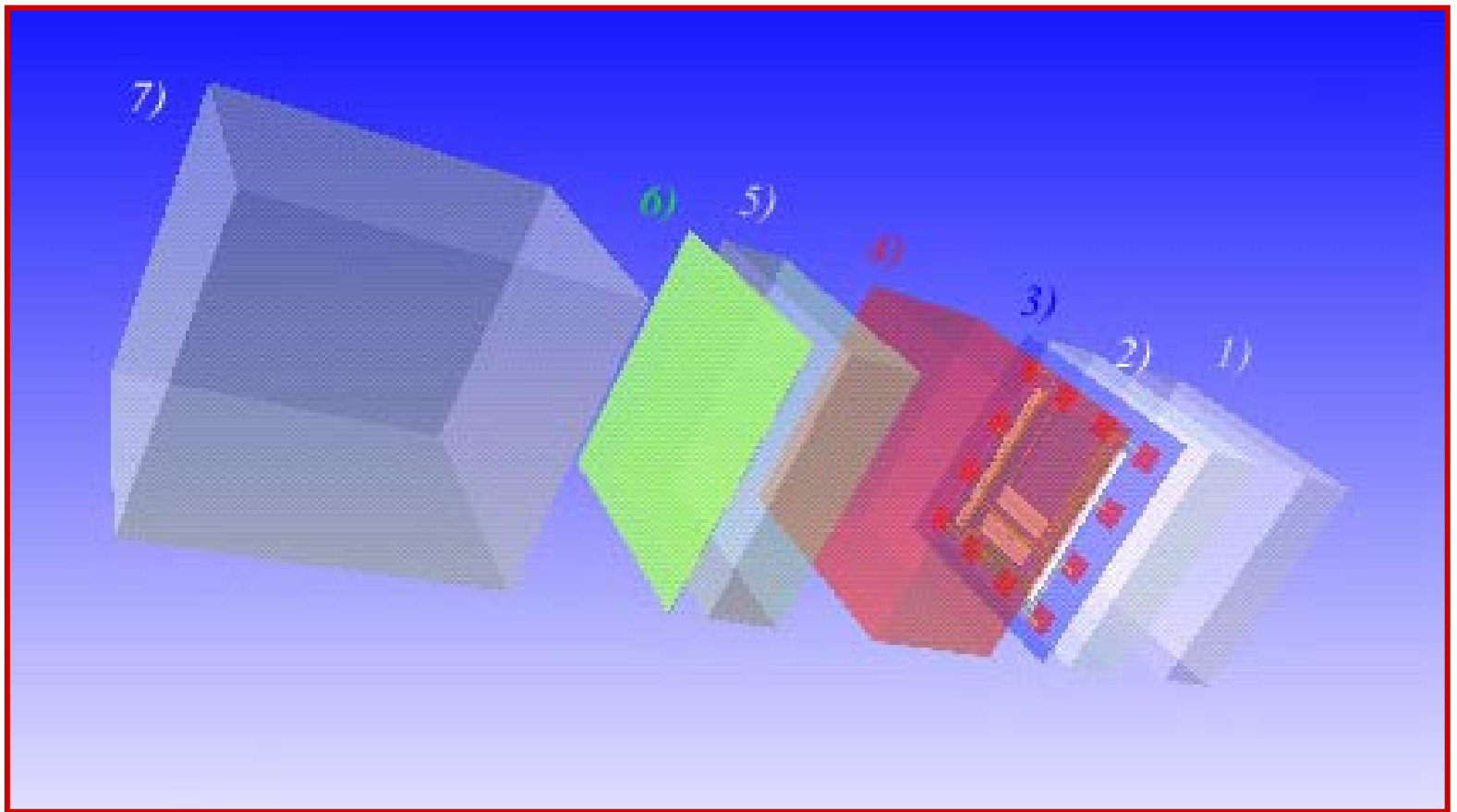


There are four RadFET on each device.



400NM implanted gate oxide devices.

Exploded view



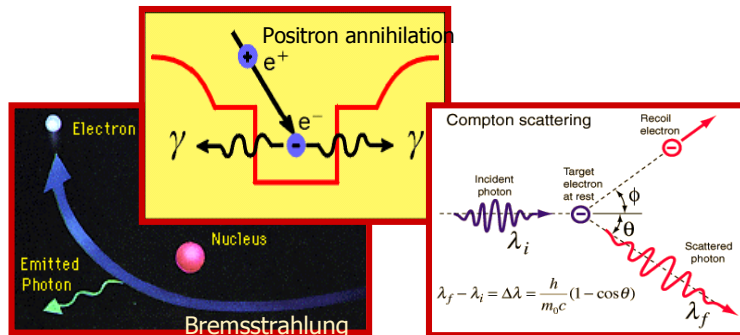
Package: lid (1), adhesive(5), the attach pad(6) and the base (7)



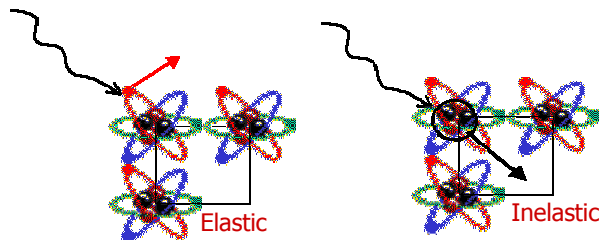
The simulated and tested devices are composed of:

- 1) Package lid - Th: 250 μm ; Kovar (Ni, Co, Fe);
- 2) Package cavity - Th: 250 μm ;
- 3) RadFET Die - Th: 1.5 μm ;
- 4) Substrate - Th: 500 μm ;
- 5) Die attach adhesive - Th: 250 μm ; (Ag, SiO₂)
- 6) Die attach pad - Th: 3.75 μm ;
- 7) Package base - Th: 1000 μm ; (Al₂O₃);

Geant4 Physics Models and Data Sources:



- **Standard and Low energy Electromagnetic:** Ionisation; δ -ray production; Multiple scattering; Bremsstrahlung; Annihilation; Photoelectric effect; Gamma conversion; Compton scattering; Rayleigh scattering; Pair-production; Atomic relaxation.

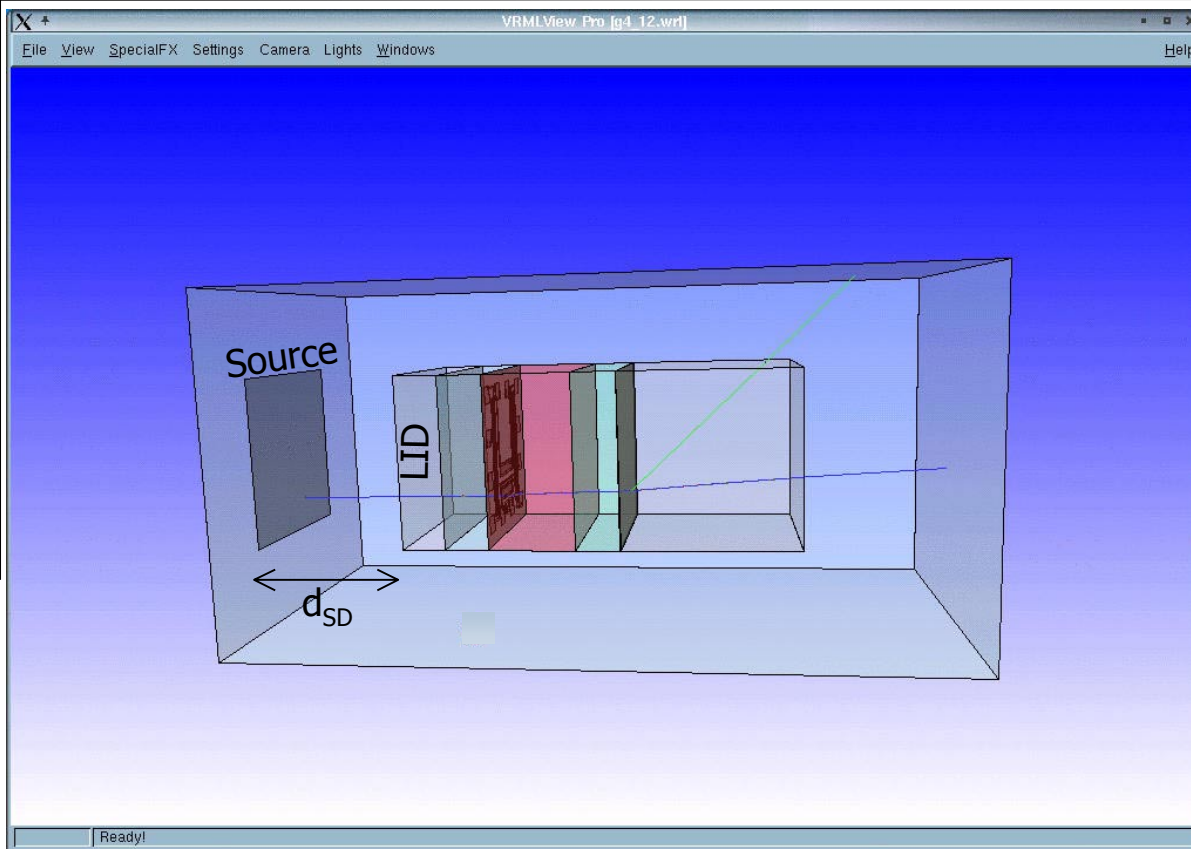


- **Low and High Energy Hadronic Shower:** Elastic and Inelastic interactions for different hadrons (protons, neutrons, tritons, deuterons,...) targeting particles from 10MeV up to some GeV.

Physics Models limitations:

These models do not allow secondary heavy ions tracking!

Simulation Scheme

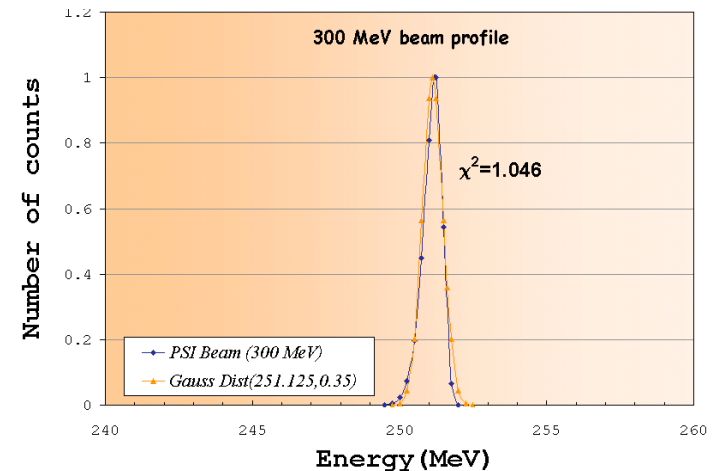
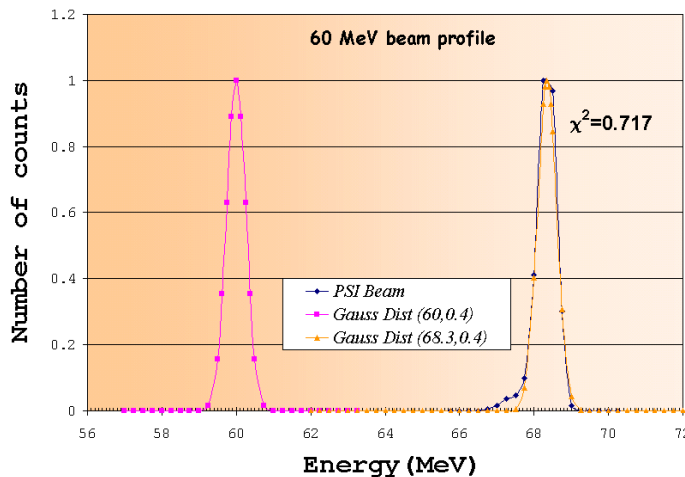
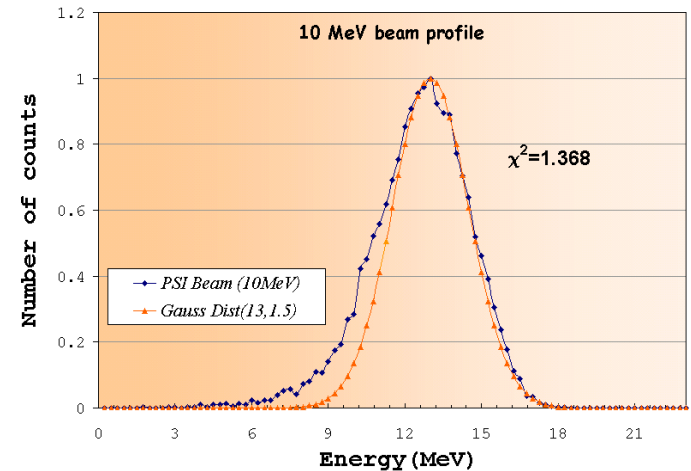


- Geant Version: 4.4.0.3
- Cut Value: $1\mu\text{m}$
- Source: 1mm^2
- Device: 1mm^2
- Source/Device dis.: $d_{SD}=10\text{cm}$
- Air
- Detector: RadfFET1' Gate Oxide
- Package conf:
 - Lid
 - No Lid

Simulated vs. PSI Proton Beams



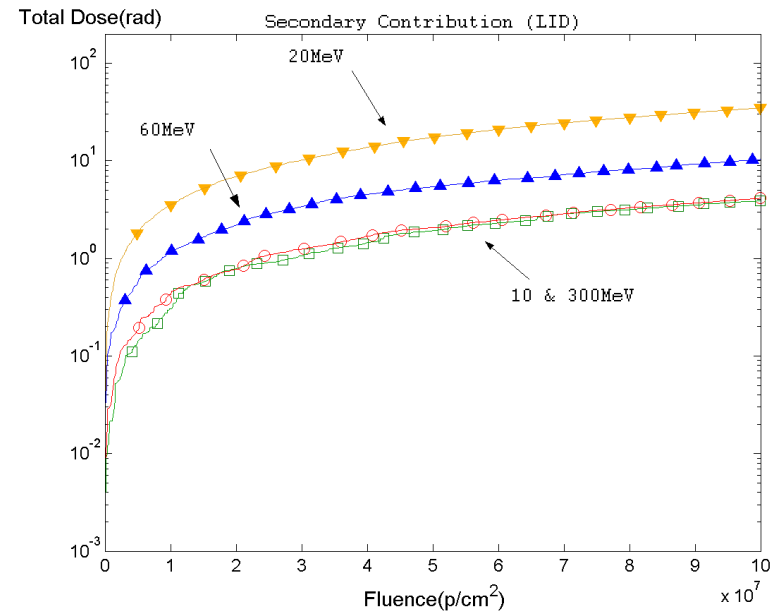
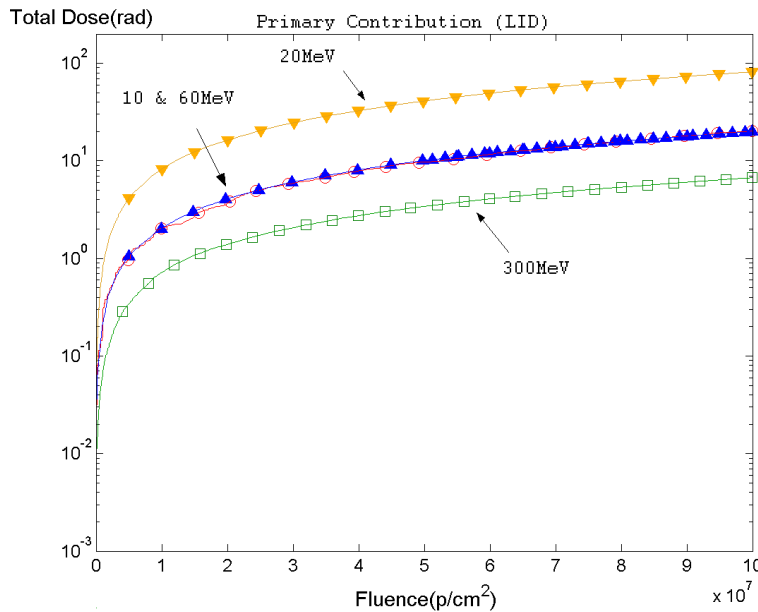
- PSI **10 MeV** beam – (>13MeV) gaussian beam : $\mu=13\text{MeV}$ and $\sigma= 1.5\text{MeV}$
- PSI **60 MeV** beam - gaussian beam with peak at 68 MeV. - Simulated : $\mu= 60\text{MeV}$ and $\sigma= 0.4 \text{ MeV}$.
- PSI **300 MeV** beam - gaussian distribution: $\mu= 251\text{MeV}$ and $\sigma= 0.26\text{MeV}$



LID Simulated Response to Proton Irradiation



"LID"

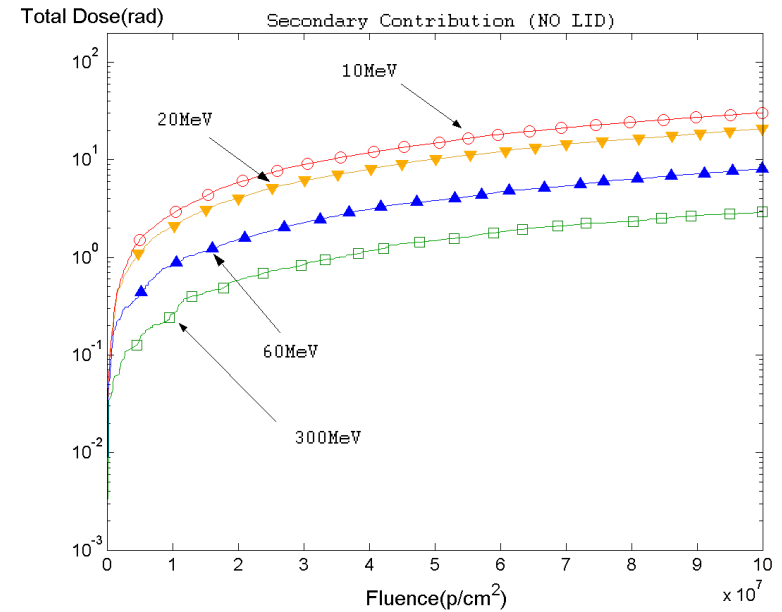
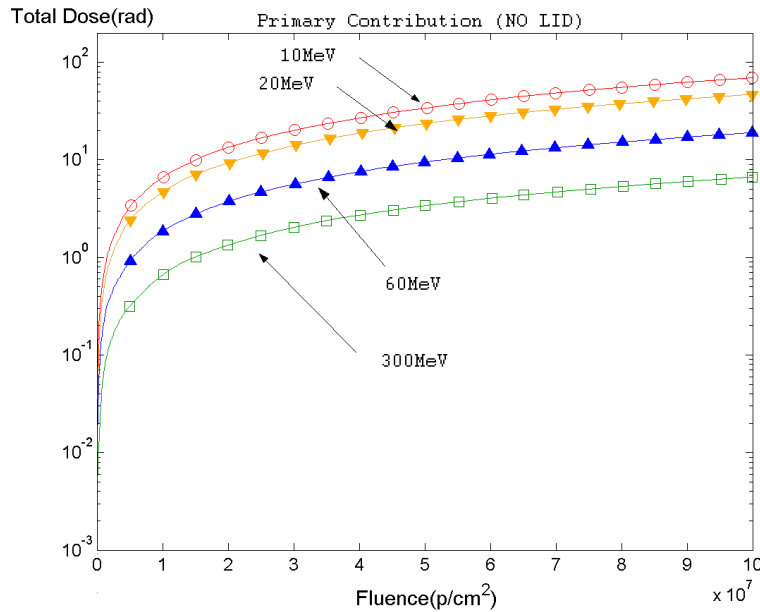


- Primary & Secondary TID \sim Function(Proton energy)
- Except for 10MeV

NO LID Simulated Response to Proton Irradiation



"NO LID"



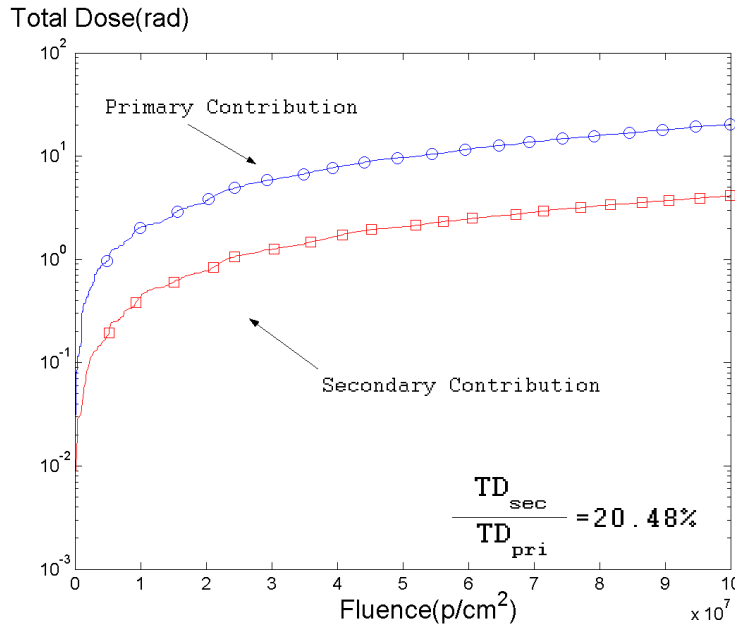
■ Primary & Secondary TID ~ Function(Proton energy)

LID Configuration

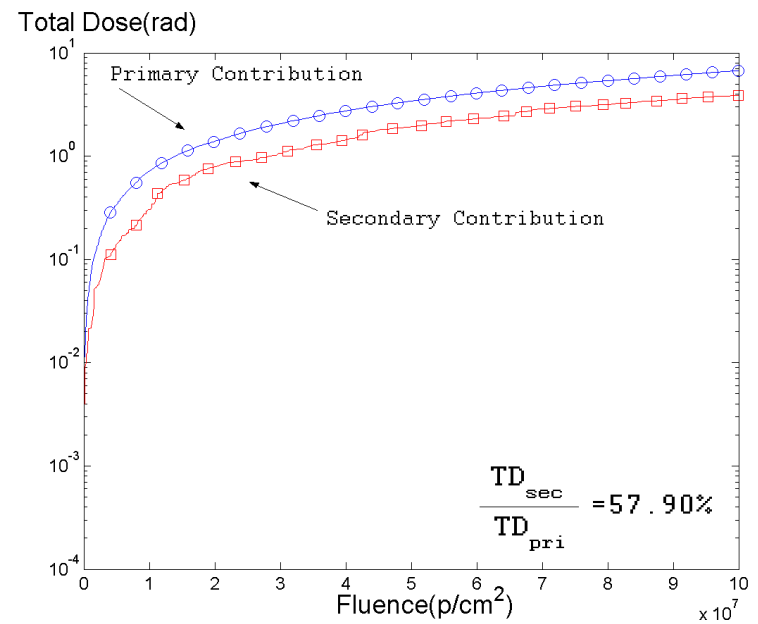
Primary and Secondary



10MeV: "LID"



300MeV : "LID"



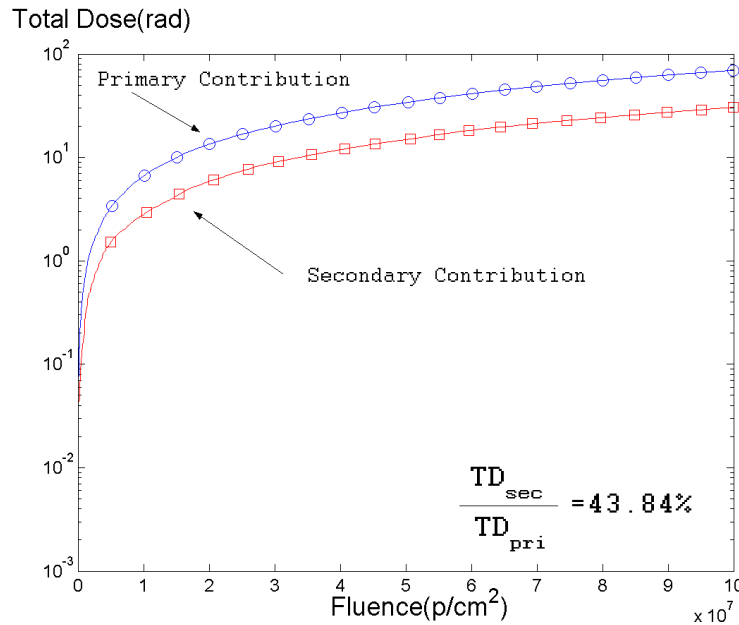
- 20% for 10 MeV
- 43% for 20MeV
- 52% for 60 MeV
- 58% for 300 MeV

LID Sec/Pri ratios of TID contribution
dependent on primary proton energy

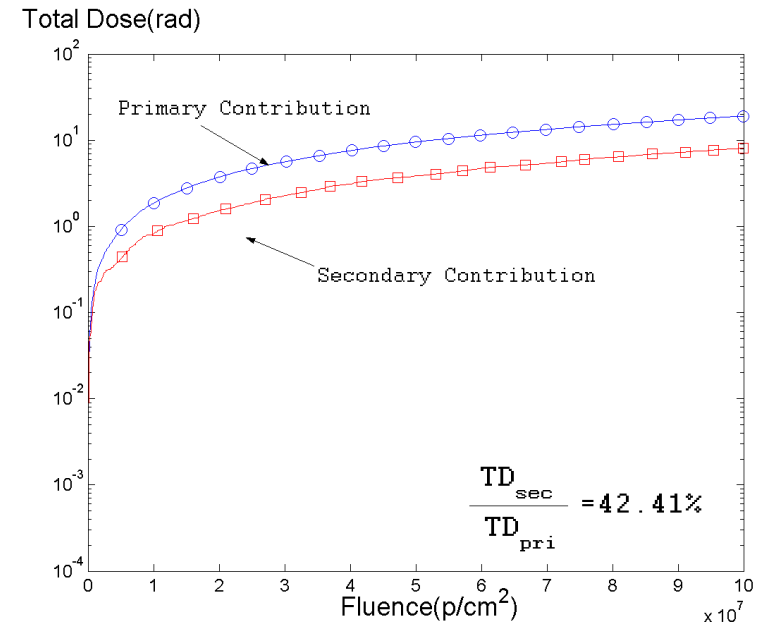
NO LID Configuration Primary and Secondary



10MeV: "NO LID"



60MeV : "NO LID"



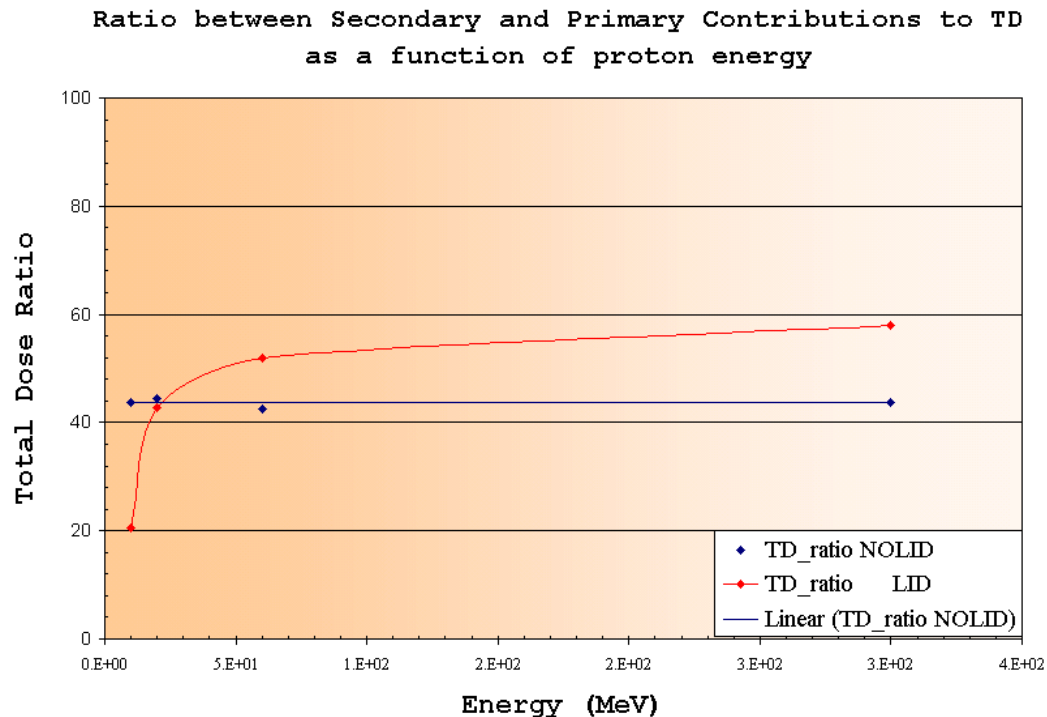
- 44% for 10 MeV
- 44% for 20 MeV
- 43% for 60 MeV
- 44% for 300 MeV

NO LID Sec/Pri ratios of TID contribution
Constant with primary proton energy

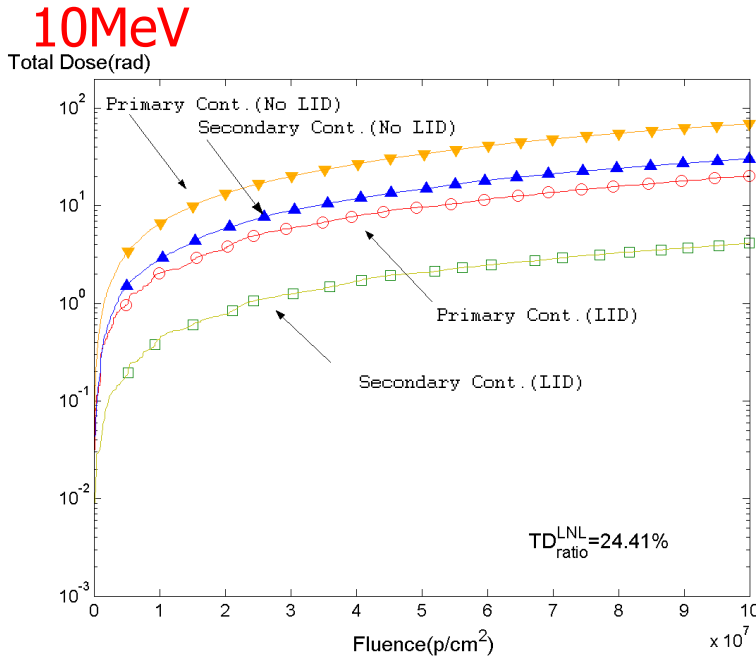
Package effect: Secondary Contribution to TID



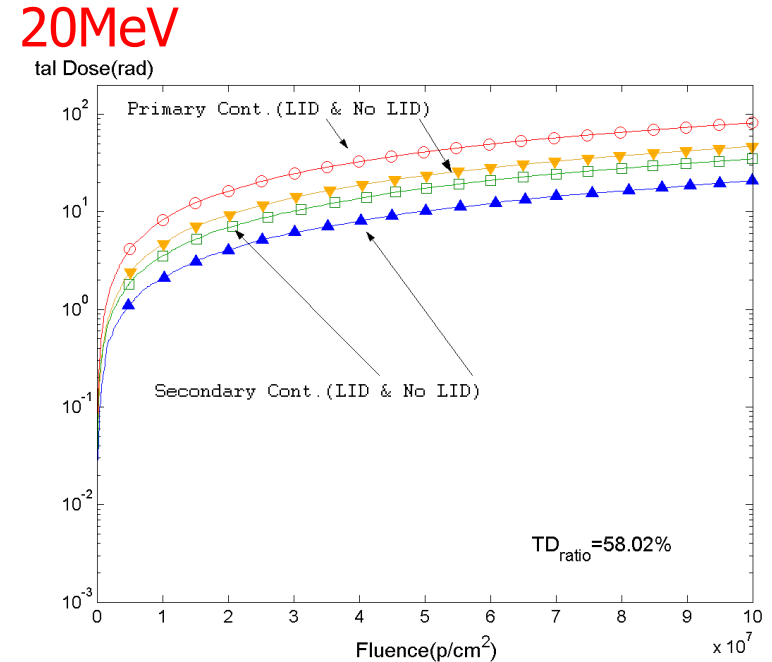
- RadFET response to secondary particles is dependent on the packaging
- LID Configuration ratios depend on Proton Initial Energy



Package effect: Secondary Contribution to TID



- “No Lid” configuration TID contributions is higher than “LID”

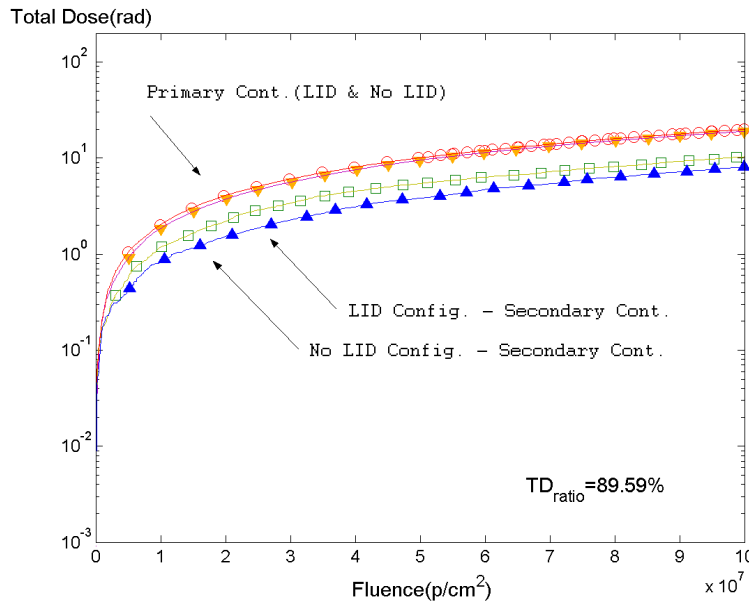


- “No Lid” configuration TID contributions is lower than “LID”

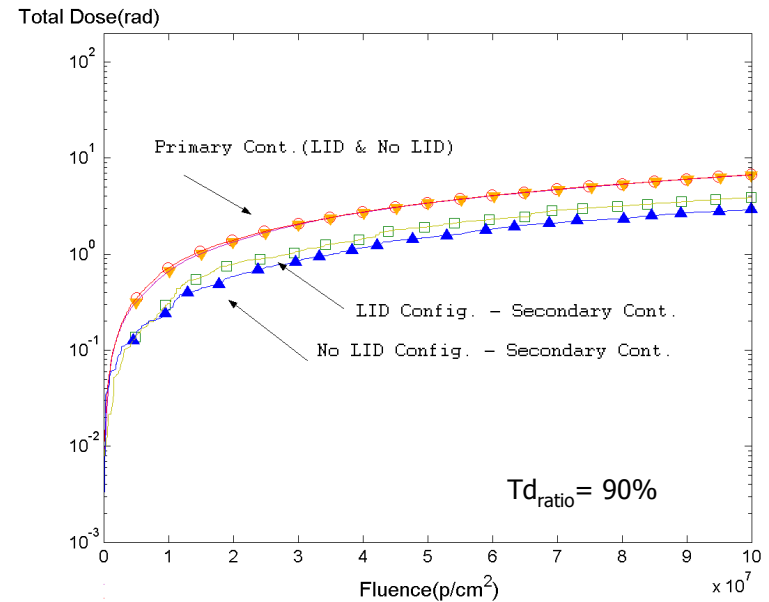
Package effect: Secondary Contribution to TID



60MeV

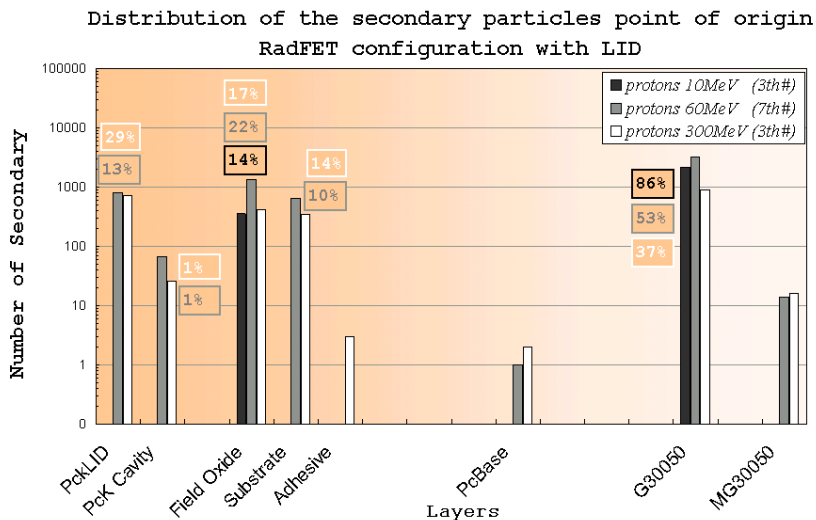


300MeV



- Secondary contribution - lower for the "No Lid" configuration 20, 60 and 300 MeV

Secondary Particles



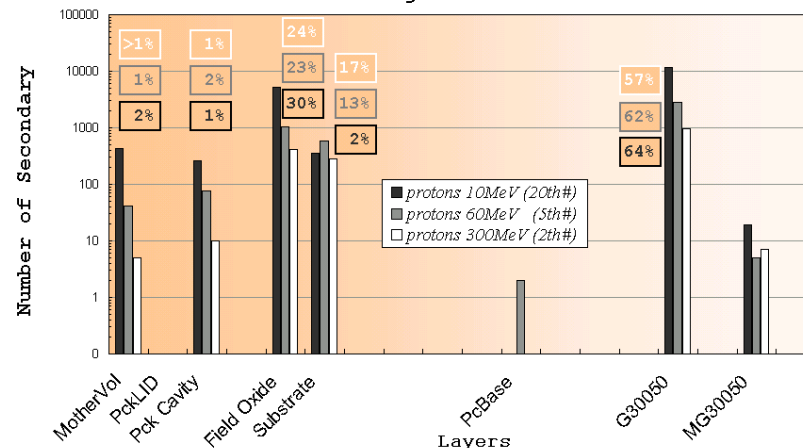
Significant contributors

- Layers very close to the gate oxide, substrate and in the package lid
- Air layer (Package cavity) (60 and 300MeV)

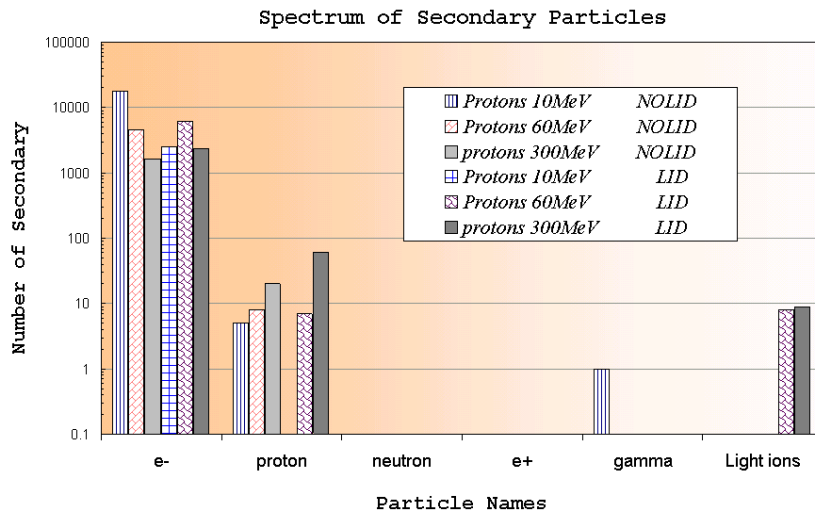
- substrate/lid secondaries - absorbed or stopped before the gate oxide.

(10 MeV)

Distribution of the secondary particles point of origin
RadFET configuration with NO LID



Secondary Particles



Major contributors :

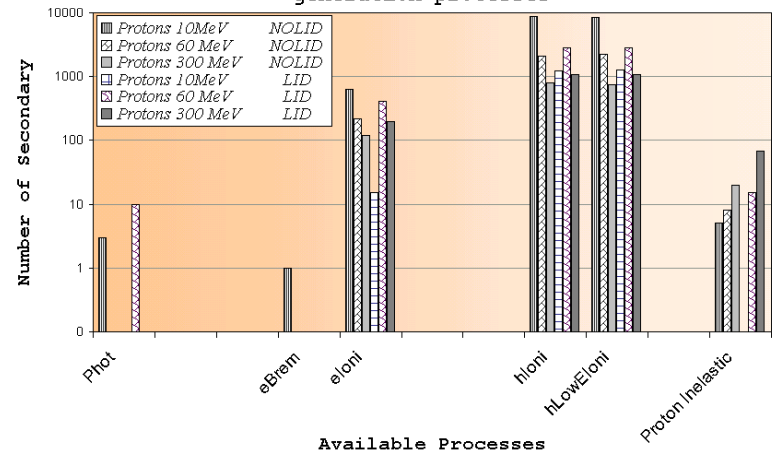
- Electrons
- Protons (not for "LID" 10 MeV)

For 60 & 300 MeV "LID"

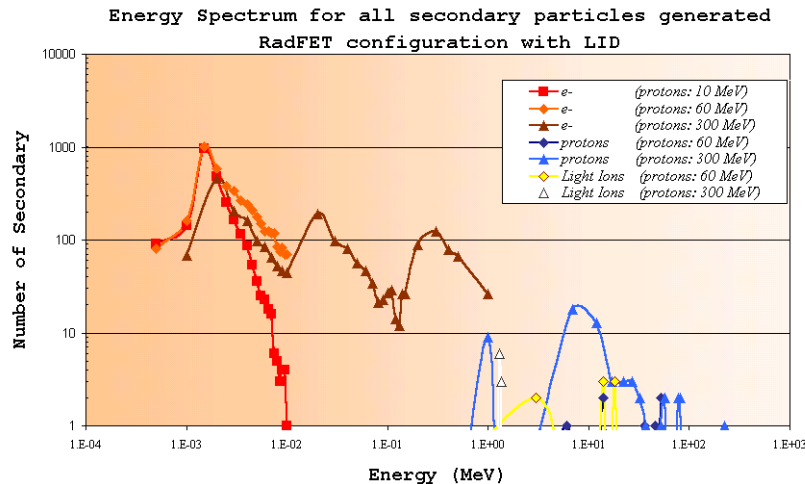
- Light ions

- electrons - by ionisation & photoelectric effect.
- protons & light ions - by means of inelastic interactions.

secondary as a function of secondary particle generation processes



Secondary Particles

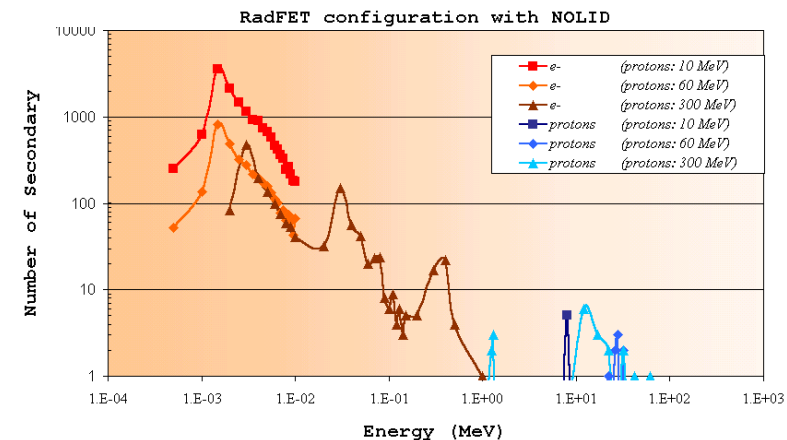


Most energetic "LID" :

- Protons
 - Light ions
- (60 and 300 MeV)

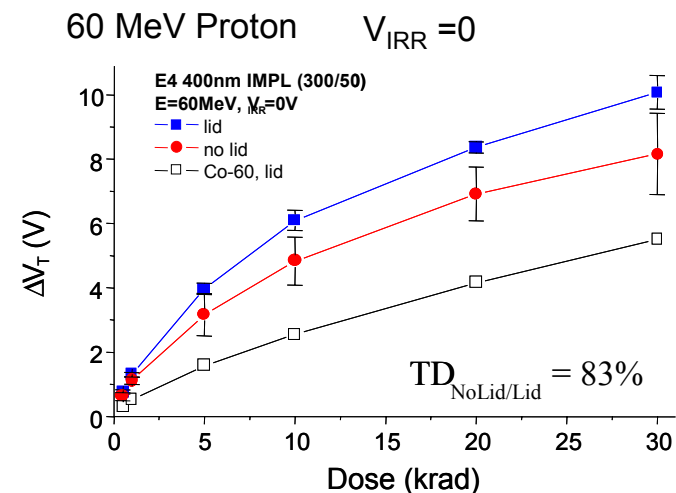
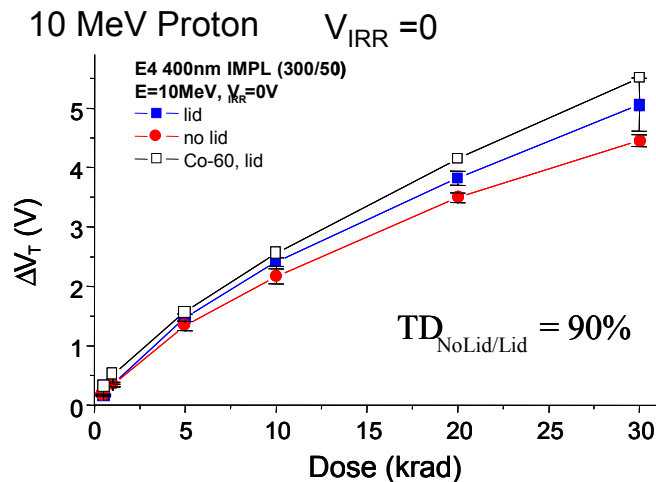
Most energetic "NOLID" :

- Protons
- (10, 60 and 300 MeV)



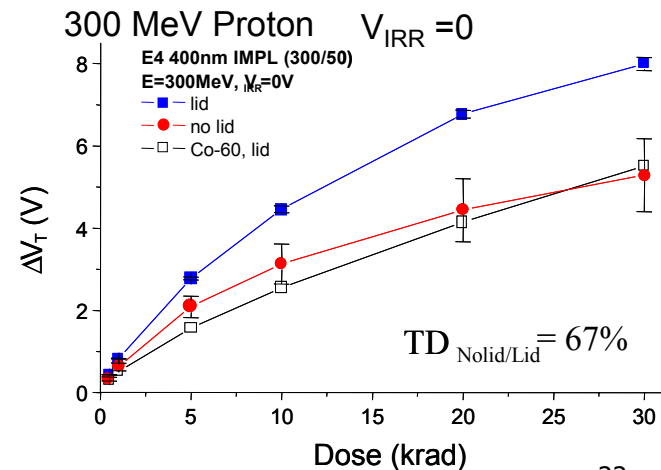


Experimental Results

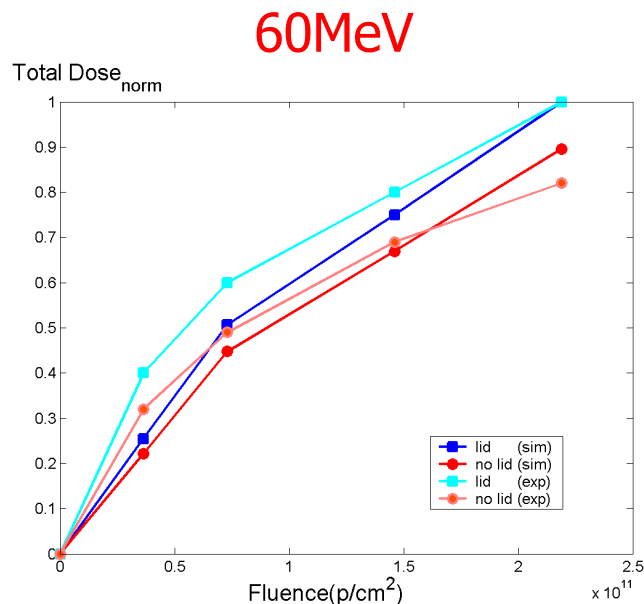


Experimental ratio bt **NOLID** & **LID** :

- 90% for 10MeV
- 83% for 60MeV
- 67% for 300MeV



Comparing Experimental & Simulation Results

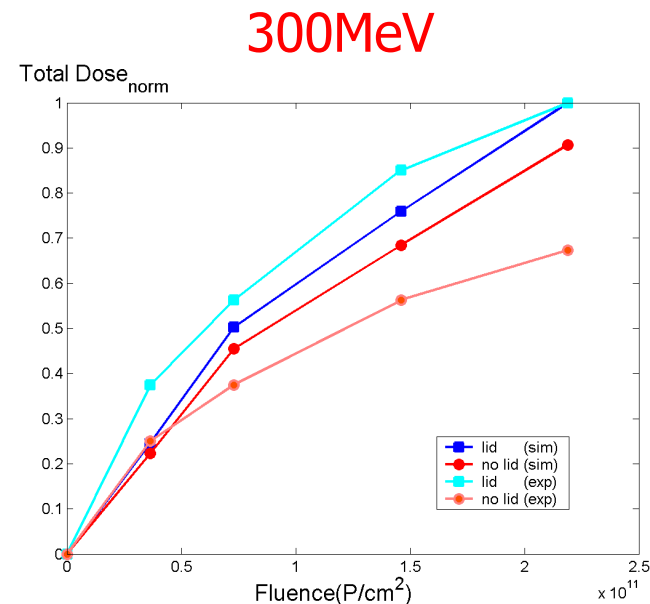


Simulation difference bt **LID** & **NOLID**

■ 11%

Experimental:

■ 18%



Simulation difference bt **LID** & **NOLID**

■ 10 %

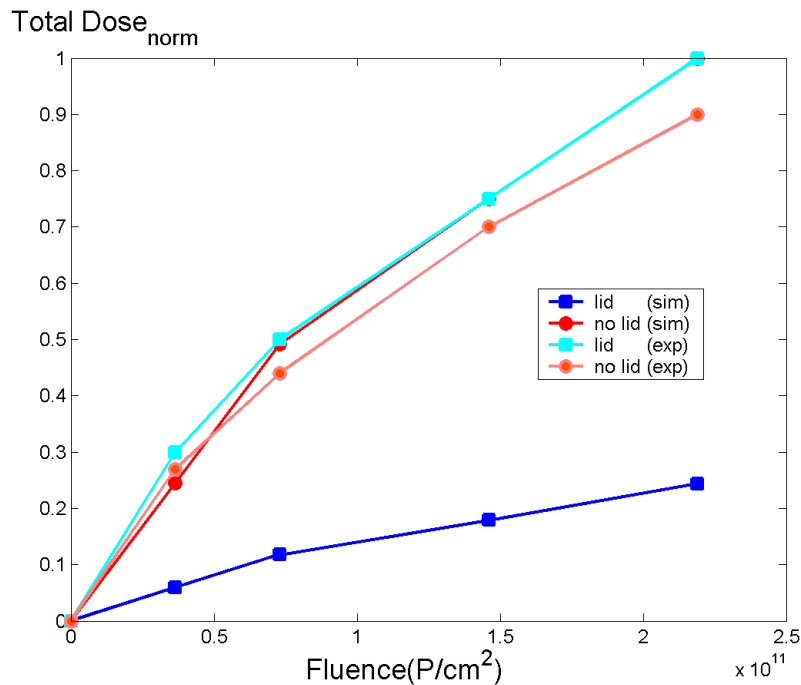
Experimental:

■ 30%

Comparing Experimental & Simulation Results



10MeV



Simulation:

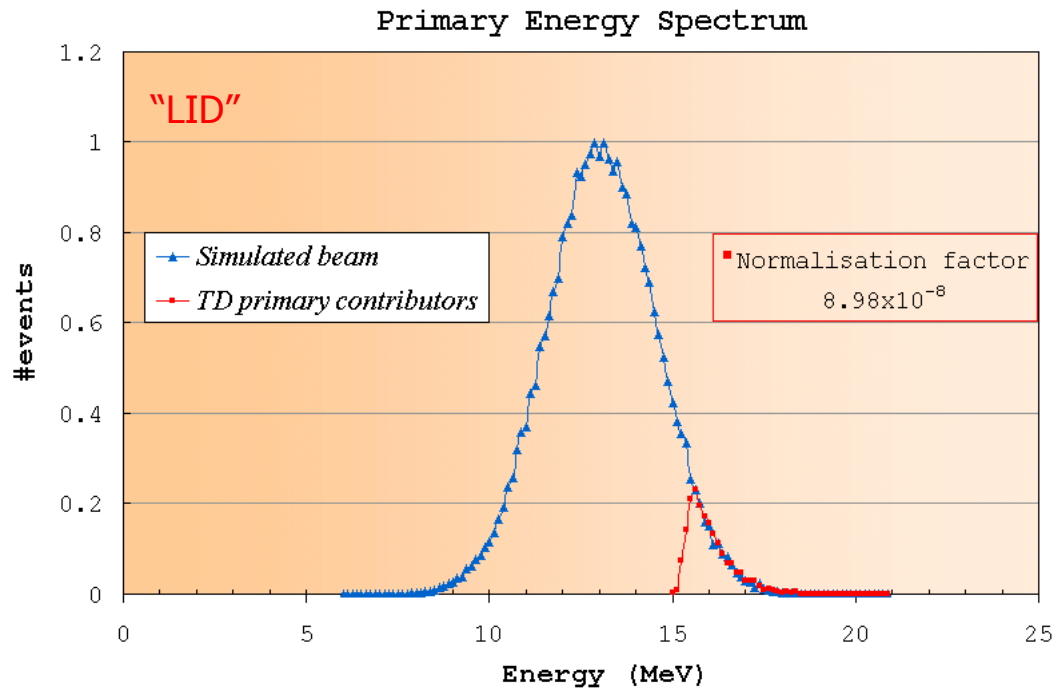
■ 24%

Experimental:

■ 10%

Simulation: **NOLID** > **LID** !

10 MeV Case



- Only protons > 15MeV - cross the source/device air, LID
- And deposit energy in the gate oxide!

GEANT4 toolkit – simulate effects of secondary particles on RadFET TID response

- Gate Oxide, Field Oxide, Lid and Substrate - main contributors to TID deposited in the RadFET gate oxide.
- Electrons & Protons – major secondary particles contributors. However, light ions (deuterons & tritons) also contribute.
- Secondary heavy ions – not considered by the models employed. But the TID contribution is believed to be marginal!
- The dominant cause of the discrepancies observed in the proton irradiation results obtained experimentally appear to be due to contribution of secondary particles generated in the Gate Oxide.



Further work

- Check for dose dependence – simulating different source-device distances (air);
- More realistic energy deposition calculations may be performed if oxide doping is included in the simulations;
- Radiation effects on components may benefit with the implementation of GEANT4 *Charge Recombination Models*